

Notice of References Cited	Application/Control No. 10/589,994		Applicant(s)/Patent Under Reexamination SMITH ET AL.	
	Examiner COLLEEN M. RAPHAEL		Art Unit 1724	Page 1 of 2

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-4,772,775 A	09-1988	Leach, Sam L.	219/121.36
*	B	US-5,866,753 A	02-1999	Deam et al.	204/157.15
*	C	US-6,038,853 A	03-2000	Penetrante et al.	422/186.03
*	D	US-6,139,694 A	10-2000	Rogers et al.	204/177
*	E	US-2002/0012618 A1	01-2002	Bromberg et al.	422/190
*	F	US-6,395,144 B1	05-2002	Yi et al.	204/164
*	G	US-6,517,794 B2	02-2003	Gieshoff et al.	204/157.3
*	H	US-6,620,394 B2	09-2003	Uhm et al.	423/240R
*	I	US-6,635,228 B1	10-2003	Moore et al.	422/186.04
*	J	US-6,696,662 B2	02-2004	Jewett et al.	204/298.38
*	K	US-6,888,040 B1	05-2005	Shufflebotham et al.	95/116
*	L	US-6,962,679 B2	11-2005	Josephson et al.	423/241
*	M	US-7,220,396 B2	05-2007	Aardahl et al.	423/240R

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
	U	Radoiu, "Studies of 2.45 GHz Microwave Induced Plasma Abatement of CF ₄ ," Environ. Sci. Technol. 2003, 37, pp. 3985-3988			
	V	Xu et al, "Plasma abatement of perfluorocompounds in inductively couple plasma reactors," J. Vac. Sci. Technol. A 18(1), Jan/Feb 2000, pp.213-231			
	W	Tonnis et al, "Inductively coupled, point-of-use plasma abatement of perfluorinated compounds and hydrofluorinated compounds from etch processes utilizing O ₂ and H ₂ O as additive gases," J. Vac. Sci. Technol. A 18(2), Mar/Apr 2000, pp. 393-400			
	X	Vitale et al, "Abatement of C ₂ F ₆ in RF and microwave plasma reactors," J. Vac. Sci. Technol. A 18(5), Sept./Oct. 2000, pp. 2217-2223			

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

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	A	US-			
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	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Radoiu, "Studies on atmospheric plasma abatement of PFCs," Radiation Physics and Chemistry 69 (2004), pp. 113-120
	V	Hartz et al, "Innovative Surface Wave Plasma Reactor Technique for PFC Abatement," Environ. Sci. Technol. 1998, 32, pp. 682-687
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.